

Lecture 14, Feb 11, 2022

Dislocations Continued

- Close-packed planes and directions are preferred when dislocations propagate since the least work is required
- In FCC there are many close-packed planes/directions; in HCP there's only one close-packed plane (the basal plane); BCC is not close packed
- Stacking faults (planar defect): for FCC an error in the packing can happen, e.g. ABCABABC

Diffusion

- Diffusion: Mass transport by atomic motion
- Diffusion occurs in fluids this happens through Brownian motion and occurs in solids through atomic movement via vacancies or interstitials
- Inter-diffusion: In an alloy atoms migrate from regions of high concentration to regions of low concentration
 - This smoothes out the concentration profile
- Self-diffusion: Atoms also migrate in an elemental solid (solid of one material!)
- Diffusion mechanisms:
 - Vacancy diffusion:
 - * There's always a finite concentration of vacancies
 - * Atoms around a vacancy jump into the vacancy so the atoms or the vacancy moves around
 - * The rate depends on the concentration of vacancies (cost to form vacancies) and the activation energy for the exchange (cost to do the exchange)
 - Interstitial diffusion:
 - * Smaller atoms of the impurity diffuse between host atoms
 - * Interstitial atoms jump between spaces
 - * Spaces are typically not close-packed so there is ample space
 - * The interstitial atoms are typically not bound to the actual crystal structure so the cost of moving is a lot lower, and interstitial diffusion happens a lot faster

Processing Using Diffusion

- Case hardening: Diffusing carbon atoms into the host iron atoms at the surface (e.g. a case hardened gear)
 - The carbon in the structure makes the iron (steel) harder
 - Carbon strains the bonds (stretches the lattice) to make the crystal harder as the surface is under tension
- Doping: Diffusing phosphorus and other impurities into silicon crystals to make semiconductors
 - Phosphorus is deposited on the surface using a mask pattern
 - The silicon is heated and the phosphorus diffuses into the silicon

Quantifying Diffusion

- To measure the rate of diffusion we use flux J , the mass (or moles of atoms) diffusing per unit area per unit time, in units of $\frac{\text{mol}}{\text{cm}^2\text{s}}$ or $\frac{\text{kg}}{\text{m}^2\text{s}}$
- Flux is measured empirically
 - Membrane of known surface area is made and a concentration gradient is imposed on the two sides
 - The speed of diffusion through this membrane is measured
 - $J = \frac{M}{At} = \frac{I}{A} \frac{dM}{dt}$ where M is the mass diffused, t is the time passed
- Steady state diffusion: When the rate of diffusion independent of time
 - Fick's first law of diffusion: $J = -D \frac{dC}{dx}$

- * The minus sign is because things diffuse from high concentration to low
 - The flux is proportional to the concentration gradient
 - If linear this is approximately $\frac{\Delta C}{\Delta x}$
- Example: Chemical protective clothing
 - e.g. Gloves are used to protect against methylene chloride; if Butyl rubber gloves (0.04cm) thick are used, what is the diffusive flux of methylene chloride through the gloves?
 - * Surface concentrations $C_1 = 0.44\text{g/cm}^3, C_2 = 0.02\text{g/cm}^3$
 - * Diffusion coefficient given
- Diffusion coefficient increases with increasing temperature as atoms have more energy
 - $D = D_0 e^{-\frac{Q_d}{RT}}$ where Q_d is the activation energy, R is the ideal gas constant (note temperature is in Kelvin)